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PATENT APPLICATION

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant:	CHOI et al.	Examiner:	Unassigned
Serial No.:	10/728,070	Group Art Unit:	1754
Filed:	December 4, 2003	Docket No.:	STFD.055PA (S02-302)
Title:	CARBON NANOTUBE GROWTH		

CERTIFICATE UNDER 37 CFR 1.8: The undersigned hereby certifies that this correspondence and the papers, as described hereinabove, are being deposited in the United States Postal Service, as first class mail, in an envelope addressed to: Commissioner for Patents, P.O. Box 1450, Alexandria, VA 22313-1450, on November 19, 2004.

By:

Jerikaifer L. Larson

INFORMATION DISCLOSURE STATEMENT (37 C.F.R. §1.97(b))

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Dear Sir:

Applicant respectfully submits the items of information on the enclosed Form 1449 for the attention of the Examiner in the above-identified application.

This statement should be considered because it is submitted either within three months of the filing date or before the first Office Action of the above-identified application. Accordingly, no fee is due for consideration of the items listed on the enclosed Form 1449.

In accordance with 37 C.F.R. §1.98(a)(2), and the 05 August 2003 Official Gazette Notice, only a copy of each foreign document or non-U.S. patent/application listed on the enclosed Form 1449 is provided.

Applicant would like to bring to the attention of the Examiner the following references, which were mentioned in the underlying provisional application:

1. Joselevich, E.; Lieber, C. M. *Nano Lett.* 2002, 2, 1137-1141.
2. Li, Y.; Kim, W.; Zhang, Y.; Rolandi, M.; Wang, D.; Dai, H. *J. Phys. Chem.* 2001, 105, 11424-11431.
3. Choi, H.; Kim, W.; Wang, D.; Dai, H. *J. Phys. Chem.* 2002, *in press*.
4. Kim, W.; Choi, H. C.; Shim, M.; Li, Y.; Wang, D.; Dai, H. *Nano Lett.* 2002, 2, 703-708.
5. Brown, K. R.; Natan, M. J. *Langmuir* 1998, 14, 726-728.
6. Zhang, Y.; Li, Y.; Kim, W.; Wang, D.; Dai, H. *Appl. Phys. A* 2002, 74, 325-328.
7. Hair, M. L. *Infrared Spectroscopy in Surface Chemistry*; Marcel Dekker, Inc.: New York, 1967.
8. The reduction potential of AuCl_4^- is +1.002 V (vs NHE) and $E_{1/2}$ of NH_2OH is -0.4 V (vs NHE). Reduction potential of Fe(III) to Fe(II) is +0.771 and Fe(II) to Fe(0) is -0.447 V (vs NHE). See Bard, A. J., Ed. *Encyclopedia of Electrochemistry of the Elements*; Marcel Dekker, Inc.: New York, 1975; Vols. 4 and 8.
9. Bengtsson, G.; Froneus, S.; Bengtsson-Kloo, L. *J. Chem. Soc., Dalton Trans.* 2002, 2548-2552.
10. Iijima, S. & Ichihashi, "T. Single-shell Carbon Nanotubes of 1-nm Diameter," *Nature* 363, 603-605 (1993).

No representation is made that a reference is "prior art" within the meaning of 35 U.S.C. §§102 and 103. In addition, Applicant(s) do(es) not represent that a reference has been thoroughly reviewed or that any relevance of any portion of a reference is intended, and reserve the right to establish otherwise under 37 C.F.R. §1.131 or others.

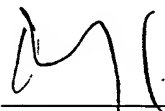
Consideration of the items listed is respectfully requested. According to M.P.E.P. § 609, Applicants requests that the Examiner return a copy of the attached Form 1449,

marked as being considered and initialed by the Examiner, to the undersigned with the next official communication.

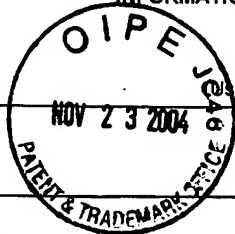
Authorization is hereby given to charge any additional fees or credit any overpayments that may be deemed necessary to Deposit Account Number 50-0996 (STFD.055PA).

Dated: November 18, 2004

Respectfully submitted,

By: 
Name: Robert J. Crawford
Reg. No.: 32,122

FORM 1449* INFORMATION DISCLOSURE STATEMENT IN AN APPLICATION (Use several sheets if necessary)	Docket Number: STFD.055PA	Application Number: 10/728,070
	Applicant: CHOI et al.	
	Filing Date: 12/4/2003	Group Art Unit: 1754



U.S. PATENT DOCUMENTS						
EXAMINER INITIAL	DOCUMENT NO.	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
FOREIGN PATENT DOCUMENTS						
	DOCUMENT NO.	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION
						YES NO
OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)						
	2001	Dai, H. In <i>Carbon Nanotubes</i> ; Dresselhaus, M. S., Dresselhaus, G., Avouris, P., Eds.; Springer: Berlin, 2001; Vol. 80; pp 29-53.				
	1998	Kong, J.; Soh, H.; Cassell, A.; Quate, C. F.; Dai, H. <i>Nature</i> 1998, 395, 878-881.				
	1999	Cassell, A.; Franklin, N.; Tombler, T.; Chan, E.; Han, J.; Dai, H. <i>J. Am. Chem. Soc.</i> 1999, 121, 7975-7976.				
	2001	Zhang, Y.; Chan, A.; Cao, J.; Wang, Q.; Kim, W.; Li, Y.; Morris, N.; Yenilmez, E.; Kong, J.; Dai, H. <i>Appl. Phys. Lett.</i> 2001, 79, 3155-3157. (abstract only)				
	2002	Ural, A.; Li, Y.; Dai, H. <i>Appl. Phys. Lett.</i> 2002, 81, 3464-3466. (abstract only)				
	1999	Soh, H.; Quate, C.; Morpurgo, A.; Marcus, C.; Kong, J.; Dai, H. <i>Appl. Phys. Lett.</i> 1999, 75, 627-629.				
	2000	Tombler, T.; Zhou, C.; Alexeyev, L.; Kong, J.; Dai, H.; Liu, L.; Jayanthi, C.; Tang, M.; Wu, S. Y. <i>Nature</i> 2000, 405, 769-772.				
	2000	Kong, J.; Franklin, N.; Zhou, C.; Chapline, M.; Peng, S.; Cho, K.; Dai, H. <i>Science</i> 2000, 287, 622-625.				
	2000	Zhou, C.; Kong, J.; Dai, H. <i>Appl. Phys. Lett.</i> 2000, 76, 1597-1599. (abstract only)				
	2002	Cheung, C.; Kurtz, A.; Park, H.; Lieber, C. <i>J. Phys. Chem.</i> 2002, 106, 2429-2433.				
	2001	Jorio, A.; Saito, R.; Hafner, J. H.; Lieber, C. M.; Hunter, M.; McClure, T.; Dresselhaus, G.; Dresselhaus, M. S. <i>Phys. Rev. Lett.</i> 2001, 86, 1118-1121. (abstract only)				
	1998	Tans, S.; Verschueren, A.; Dekker, C. <i>Nature</i> 1998, 393, 49-52.				

EXAMINER	DATE CONSIDERED
EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; draw line through citation if not in conformance and not considered. Include copy of this form for next communication to the Applicant.	